Notice of Allowability	Application No.	Applicant(s)
	10/646,658	LIANG, CHUNLIN
	Examiner	Art Unit
	Eric B. Chen	1765
The MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication IGHTS. This application is subject to	olication. If not included will be mailed in due course. THIS
1. This communication is responsive to <u>21 October 2005</u> .		
2. The allowed claim(s) is/are <u>15-26</u> .		
3. ☐ Acknowledgment is made of a claim for foreign priority unal All b) ☐ Some* c) ☐ None of the:	nder 35 U.S.C. § 119(a)-(d) or (f).	
1. Certified copies of the priority documents have		
2. Certified copies of the priority documents have	• • • • • • • • • • • • • • • • • • • •	
 Copies of the certified copies of the priority documents International Bureau (PCT Rule 17.2(a)). 	cuments have been received in this	national stage application from the
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requirements
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give		
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.		
(a) 🔲 including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached		
1) hereto or 2) to Paper No./Mail Date		
(b) including changes required by the attached Examiner's Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the		
 DEPOSIT OF and/or INFORMATION about the depo- attached Examiner's comment regarding REQUIREMENT 	sit of BIOLOGICAL MATERIAL r FOR THE DEPOSIT OF BIOLOGIC	nust be submitted. Note the AL MATERIAL.
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 D Notice of Informal P	atent Application (PTO-152)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summary	,,
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0	Paper No./Mail Dat	e
Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material		
	8. ⊠ Examiner's Stateme	ent of Reasons for Allowance
	9. Other	
	SUPER	NADINE G. MORTON VISORY L. L. L. XAMINER

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EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below: in the Abstract, consolidate the two paragraphs into a single paragraph; in the amendment to the Specification, filed Oct. 21, 2005, after "filed April 9, 1999" insert — now U.S. Patent No. 6,642,557 --.

REASONS FOR ALLOWANCE

- 2. Claims 15-26 are allowed.
- 3. The following is an examiner's statement of reasons for allowance for claim 15: the prior art fails to teach or suggest etching the exposed semiconductor substrate to form a first undercut region subjacent to the first trench and a second undercut region subjacent to the second trench wherein a top portion of the T-shaped pedestal is disposed between the first trench and the second trench and a stem portion of the T-shaped pedestal is disposed between the first undercut region and the second undercut region. The closest prior art, Burton, discloses the forming a first trench and a second trench (Figure 8A) and a single undercut region (32) (column 4, lines 22-31), rather than a stem portion of the T-shaped pedestal is disposed between the first undercut region and the second undercut region.
- 4. The following is an examiner's statement of reasons for allowance for claim 26: the prior art fails to teach or suggest a first undercut region subjacent to the first trench and a second undercut region subjacent to the second trench wherein the first undercut region is isolated from the second undercut region by a portion of the semiconductor

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substrate. The closest prior art, Burton, discloses the forming a first trench and a second trench (Figure 8A) and a single undercut region (32) (column 4, lines 22-31), rather than the first undercut region is isolated from the second undercut region by a portion of the semiconductor substrate.

5. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Response to Arguments

- 6. In view of Applicant's amendments to claim 26 (Applicant's Amendments to the Claims, page 5), filed Oct. 21, 2005, the rejection of claim 26 under 35 U.S.C. 101 as claiming the same invention as claim 12 of prior U.S. Patent No. 5,972,758 has been withdrawn.
- 7. Applicant's arguments (Applicant's Remarks, page 8), filed Oct. 21, 2005, with respect to the rejection of claims 15-25 under the judicially-created doctrine of double patenting over Liang (U.S. Patent No. 5,972,758) have been fully considered and are persuasive. Applicant has pointed out that the Liang reference does not teach or suggest "etching the exposed semiconductor substrate to form a first undercut region subjacent to the first trench and a second undercut region subjacent to the second trench wherein a top portion of the T-shaped pedestal is disposed between the first trench and the second trench and a stem portion of the T-shaped pedestal is disposed

between the first undercut region and the second undercut region" (page 8). The rejection of claims 15-25 has been withdrawn.

- 8. Applicant's arguments (Applicant's Remarks, page 8), filed Oct. 21, 2005, with respect to the rejection of claim 15 under 35 U.S.C. 103(a) as being unpatentable over Burton, in view of Wolf, in further view of Streetman, have been fully considered and are persuasive. Applicant has pointed out that the Burton reference does not teach or suggest "etching the exposed semiconductor substrate to form a first undercut region subjacent to the first trench and a second undercut region subjacent to the second trench wherein a top portion of the T-shaped pedestal is disposed between the first trench and the second trench and a stem portion of the T-shaped pedestal is disposed between the first undercut region and the second undercut region" (page 9). The rejection of claims 15-25 has been withdrawn.
- 9. Applicant's arguments (Applicant's Remarks, page 8), filed Oct. 21, 2005, with respect to the rejection of claim 26 under 35 U.S.C. 103(a) as being unpatentable over Burton, in view of Wolf, in further view of Gardner, have been fully considered and are persuasive (page 10), for similar reasons as discussed above. The rejection of claim 26 has been withdrawn.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Eric B. Chen whose telephone number is (571) 272-

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2947. The examiner can normally be reached on Monday through Friday, 8AM to

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4:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G. Norton can be reached on (571) 272-1465. The fax phone

number for the organization where this application or proceeding is assigned is 571-

273-8300.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for

published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only.

For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

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EBC

Nov. 22, 2005